

## Low-pressure plasma system

# V240-2G

## Highly precise and flexible



*The process chamber with plasma source and winding mechanism.*

The reel-to-reel system V240-2G is designed for the low-pressure plasma etching of finest structures on plastic foils and is also suitable for plasma activation and cleaning processes.

The system is equipped with two special high performance etching generators and is prepared for upgrading by two additional sources (V240-4G).

The plasma process operates during winding of the substrate.

### Available options

- Vacuum pump
- Further gas channels
- Closed circuit cooling
- Reel tempering up to 90 °C

### Technical data

Outer dimensions: approx. W 2,900 x H 2,170 x D 1,500 mm

Inner dimensions process chamber: approx. W 1,300 x H 770 x D 560 mm

Roll diameter: max. 300 mm, substrate width: max. 350 mm, roll weight: max. 25 kg

Microwave generators: 2 pcs. à 2.45 GHz, flexible power from 200 W to 2,000 W per source

Gas supply: 3 gas channels with mass flow controllers and magnetic valves

Vacuum connection: DN 100 ISO-K

Electrical connection: 230/400 V, 50/60 Hz

Process control: PLC control unit (PP 420 by B & R)

Vacuum gauge: capacitance manometer (independent of gas type)

Interfaces: Ethernet, USB

Surface treatment methods: etching, cleaning, activation

*With its three gas channels and high performance microwave generators the system V240-2G is suitable for precise etching as well as activation and cleaning processes.*



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